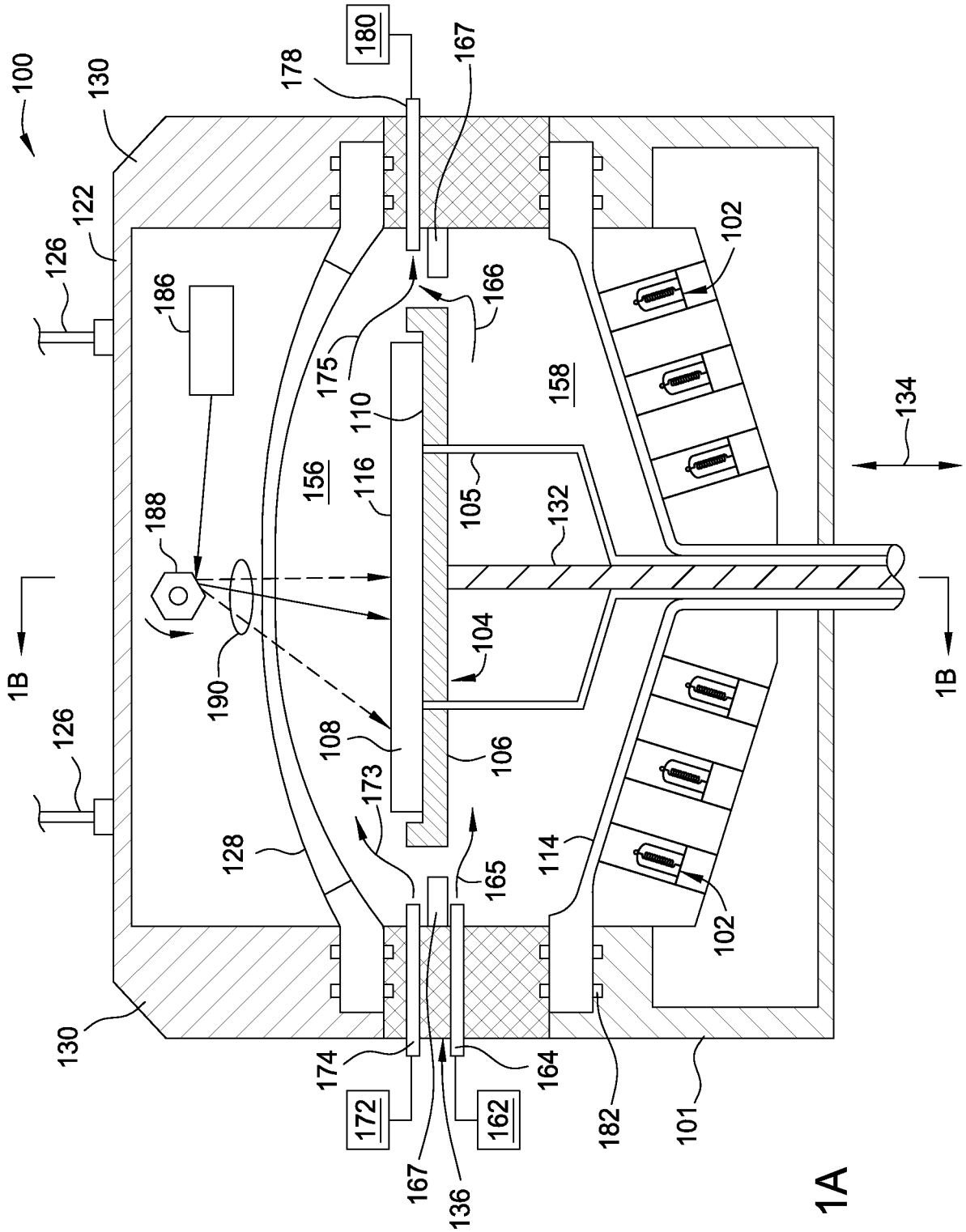

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FIG. 1A

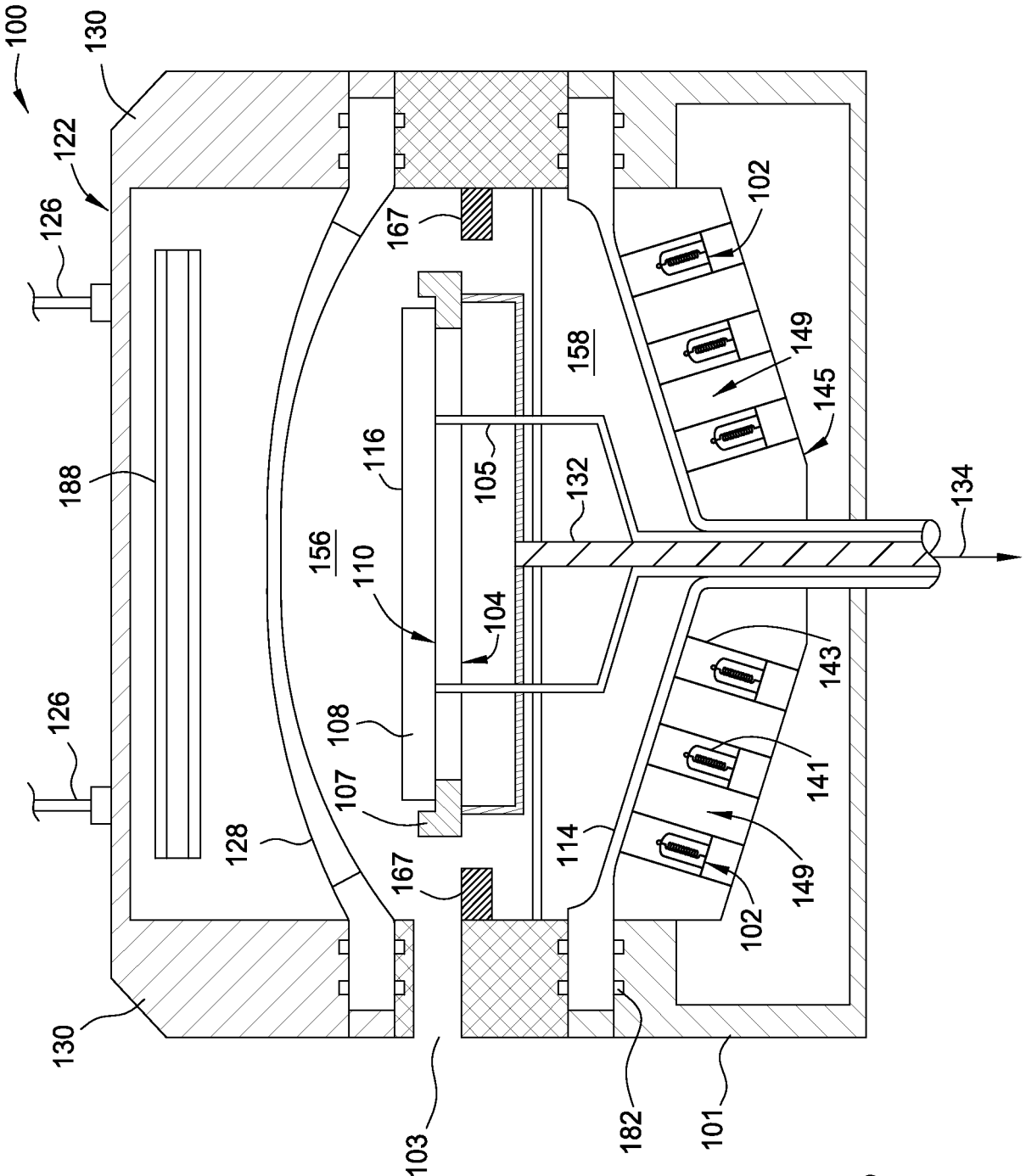

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FIG. 1B

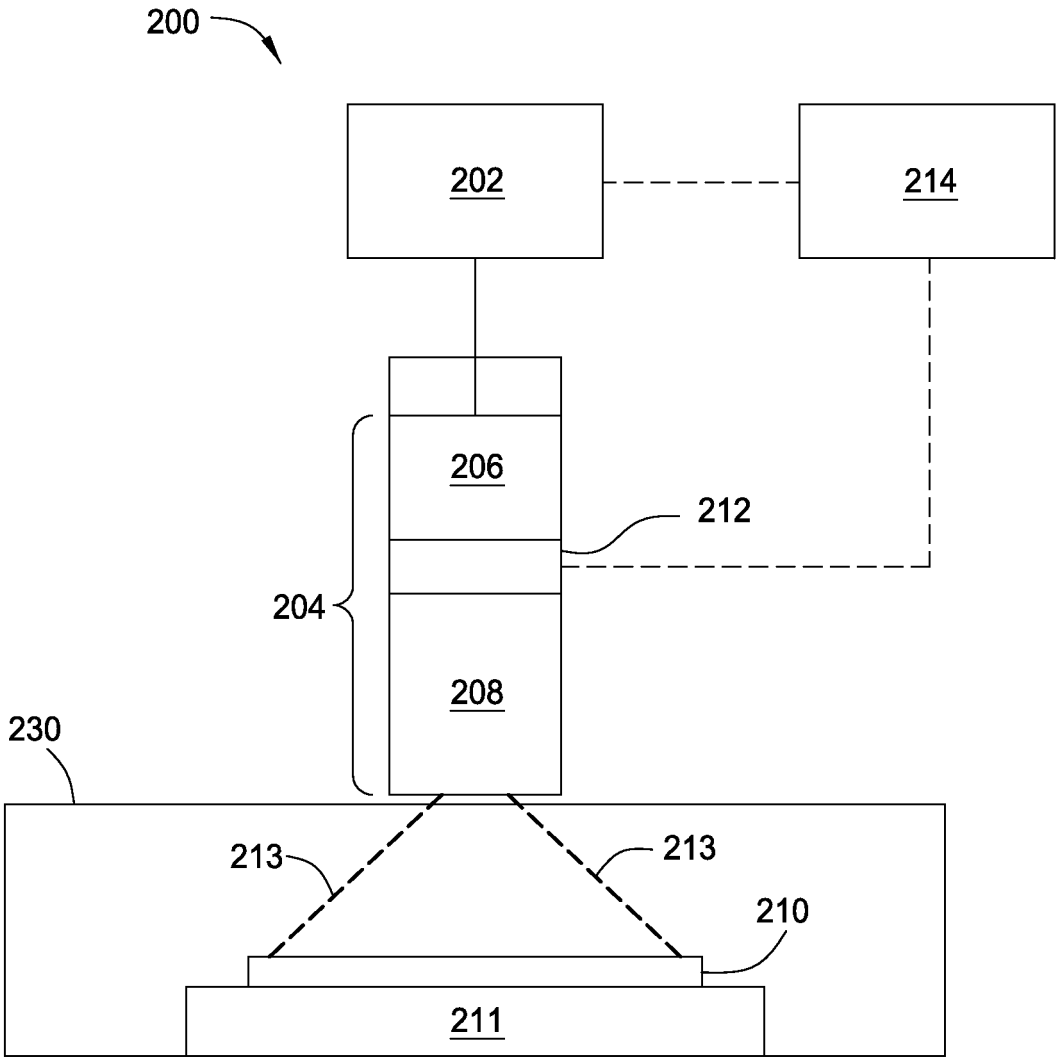


FIG. 2

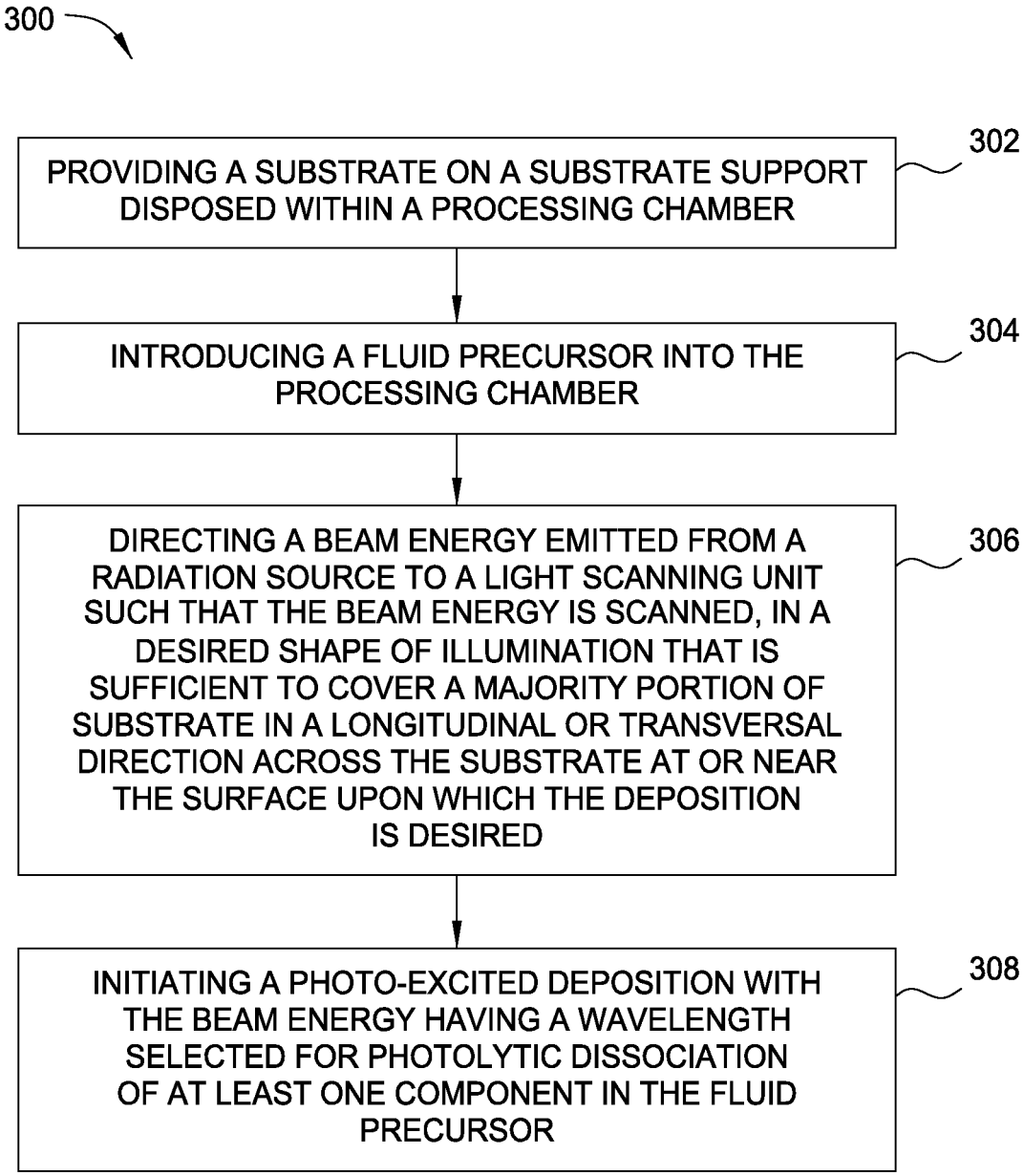

300
PROVIDING A SUBSTRATE ON A SUBSTRATE SUPPORT DISPOSED WITHIN A PROCESSING CHAMBER
302
INTRODUCING A FLUID PRECURSOR INTO THE PROCESSING CHAMBER
304
DIRECTING A BEAM ENERGY EMITTED FROM A RADIATION SOURCE TO A LIGHT SCANNING UNIT SUCH THAT THE BEAM ENERGY IS SCANNED, IN A DESIRED SHAPE OF ILLUMINATION THAT IS SUFFICIENT TO COVER A MAJORITY PORTION OF SUBSTRATE IN A LONGITUDINAL OR TRANSVERSAL DIRECTION ACROSS THE SUBSTRATE AT OR NEAR THE SURFACE UPON WHICH THE DEPOSITION IS DESIRED
306
INITIATING A PHOTO-EXCITED DEPOSITION WITH THE BEAM ENERGY HAVING A WAVELENGTH SELECTED FOR PHOTOLYTIC DISSOCIATION OF AT LEAST ONE COMPONENT IN THE FLUID PRECURSOR
308

FIG. 3